



JPW

THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:

Justin K. Brask et al.

Serial No.: 10/622,955

Filed: July 18, 2003

For: Etching Metal Silicides
and Germanides

§
§
§
§
§
§
§
§
§

Art Unit: 2811

Examiner: Sara W. Crane

Atty Docket: ITL.1021US
P16708

Assignee: Intel Corporation

Mail Stop **Amendment**
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

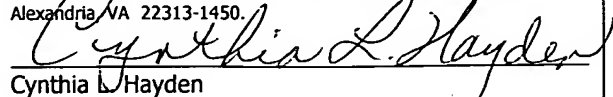
REPLY TO PAPER NO. 01102005

Sir:

In response to the office action mailed January 14, 2005, please amend the above-referenced patent application as follows:

Date of Deposit: March 15, 2005

I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.


Cynthia L. Hayden